



9th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials /
10th International Conference on Plasma-Nano Technology & Science

ISPlasma2017/IC-PLANTS2017

March 1-5, 2017
CHUBU UNIVERSITY, Aichi, JAPAN

Organizing Committee

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Sponsored by : The Japan Society of Applied Physics

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Chubu University

<http://www.isplasma.jp/>

※The photograph is an image.



Registration

Advanced Online Registration is required.

Registration Fee : Early Registration (Until Jan 31, 2017)

On-site Registration

Tutorial Fee : Participant in Main Symposium

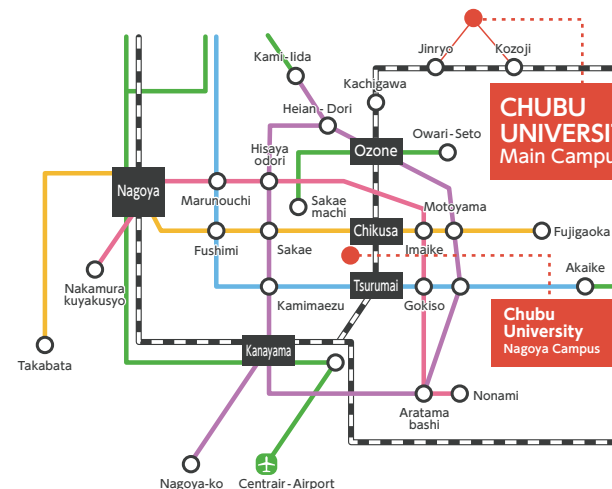
Tutorial Registration Only

Banquet Fee (on March 3, 2017)

General	Student
JPY 45,000	JPY 15,000
JPY 50,000	JPY 20,000
JPY 1,000	JPY 1,000
JPY 10,000	JPY 5,000
JPY 6,000	JPY 3,000

* Refunds cannot be made at any reason.

Access



Meitetsu Airport Line Central Japan International Airport Station

26 min. by rapid train

Meitetsu Line Kanayama Station

JR Kanayama Station

20 min. by local train

22 min. by rapid train

JR Chuo Line Jinryo Station

JR Chuo Line Kozoji Station

School bus for Chubu University

Meitetsu bus for Chubu Daigaku-mae

7 min. by School bus

10 min. by bus

Chubu University

Contact

Secretariat : Inter Group Corp.

E-mail : isplasma2017@intergroup.co.jp Website : <http://www.isplasma.jp/>

ISPlasma/IC-PLANTS is a specialized international symposium that brings together about 1,000 world-leading scientists and engineers in Nagoya, Japan to discuss latest researches in the fields of advanced plasma science, its applications for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. In this symposium biosensing technologies will be also highlighted, because of their increasing importance in healthcare, agri-food and environmental areas. We hope that this symposium will provide an ideal venue for the exchange of new ideas and information, and also support the initiation or further development of international collaborations among those who work in these multidisciplinary fields.

● Related Fields

Plasma

- Plasma Source
- Modeling & Simulation
- Thin Film Deposition Process
- Flexible Electronics
- Plasma Agriculture
- Advanced Plasma Diagnostics
- Plasma in Liquid
- Etching Process
- Plasma Biology & Medicine
- Plasma for Nano & Green Technologies

Nitride Semiconductors

- Crystal Growth of GaN & Related Materials
- Characterization
- Optical & Optoelectronic Devices
- MBE Growth & Nitrogen Source
- Device Processing
- Electron & Power Devices

Nanomaterials

- Nanodots & Nanoparticles
- 2D Nanomaterials
- Composites & Functionally Grade Materials
- Applications for Energy, Nanomedicine & Sensing
- Nanotubes, Nanowires & Nanorods
- Porous Materials & Membranes
- Surface Modification & Functionalization

Biosensing

- Detection Technologies
- Electrochemical Devices
- Biomarkers & Biosensor Surfaces
- Biomaterials
- Optical Devices, Bioimaging
- Biosensors
- Fabrication Technologies
- Biodevices, uTAS, Lab on a Chip

● Abstract Submission

Online abstract submission (one-page English) is available from <http://www.isplasma.jp/>

Submission Deadline : ~~Monday, October 3, 2016 JST~~

Friday, October 21, 2016 JST (Extended)

● Special Issue

Selected papers will be published in a special issue of a scientific journal.

● Tutorial

Tutorial for Plasma Science, Nitride Semiconductors Nanomaterials and Biosensing will be held on Wed, March 1, 13:00

PROGRAM

Plenary Speaker

Osamu Ishihara (Chubu University, JAPAN)

Keynote / Invited Speakers

Keynote Speaker

H. Nakanishi (Aichi Cancer Center Research Institute, JAPAN)

Invited Speakers

H. Ago (Kyushu University, JAPAN)

P. J. Bruggeman (University of Minnesota, U.S.A)

W. H. Choe (KAIST, KOREA)

N. Fukata (National Institute for Materials Science, JAPAN)

T. Gregorkiewicz (University of Amsterdam, THE NETHERLANDS)

I. Grzegory (Institute of High Pressure Physics of the Polish Academy of Sciences, POLAND)

H. Hayashi (TOSHIBA, JAPAN)

Y. Hirai (Kyoto University, JAPAN)

F. Horikiri (SCIOCS, JAPAN)

C. C. Hu (National Tsing Hua University, CHINA)

Y. Ichikawa (JST, JAPAN)

K. H. Jeong (KAIST, KOREA)

T. Kachi (Nagoya University, JAPAN)

Y. Kanemitsu (Kyoto University, JAPAN)

H. Kawai (POWDEC K.K., JAPAN)

M. Matsui (Shizuoka University, JAPAN)

H. van der Meiden (DIFFER, NETHERLANDS)

Y. Miyahara (Tokyo Medical and Dental University, JAPAN)

K. Naniwae (EL-Seed Corp., JAPAN)

L. L. Raja (The University of Texas, U.S.A)

J. Shiomi (The University of Tokyo, JAPAN)

R. D. Short (University of South Australia, AUSTRALIA)

J. S. Speck (University of California, USA)

E. Stamate (Technical University of Denmark, DENMARK)

Q. Sun (Chinese Academy of Sciences, CHINA)

A. Suzuki (Panasonic, JAPAN)

M. Ueda (Okayama University, JAPAN)

K-D. Weltman (INP Greifswald e.V, GERMANY)

T. Yanagida (Kyushu University, JAPAN)

S. J. Yoo (National Fusion Research Institute, KOREA)

E. Zanoni (Universita' di Padova, ITALY)

H. W. Zhu (Tsinghua University, CHINA)

Tutorial Speakers

A. Fridman (Drexel University, U.S.A)

Y. Li (China University of Petroleum, CHINA)

D. Ueda (Kyoto Institute of Technology, JAPAN)